Electronic Supplementary Material (ESI) for RSC Advances

Electronic Supplementary Information

Simple Multi-level Microchannel Fabrication by Pseudo-Grayscale Backside Diffused Light Lithography

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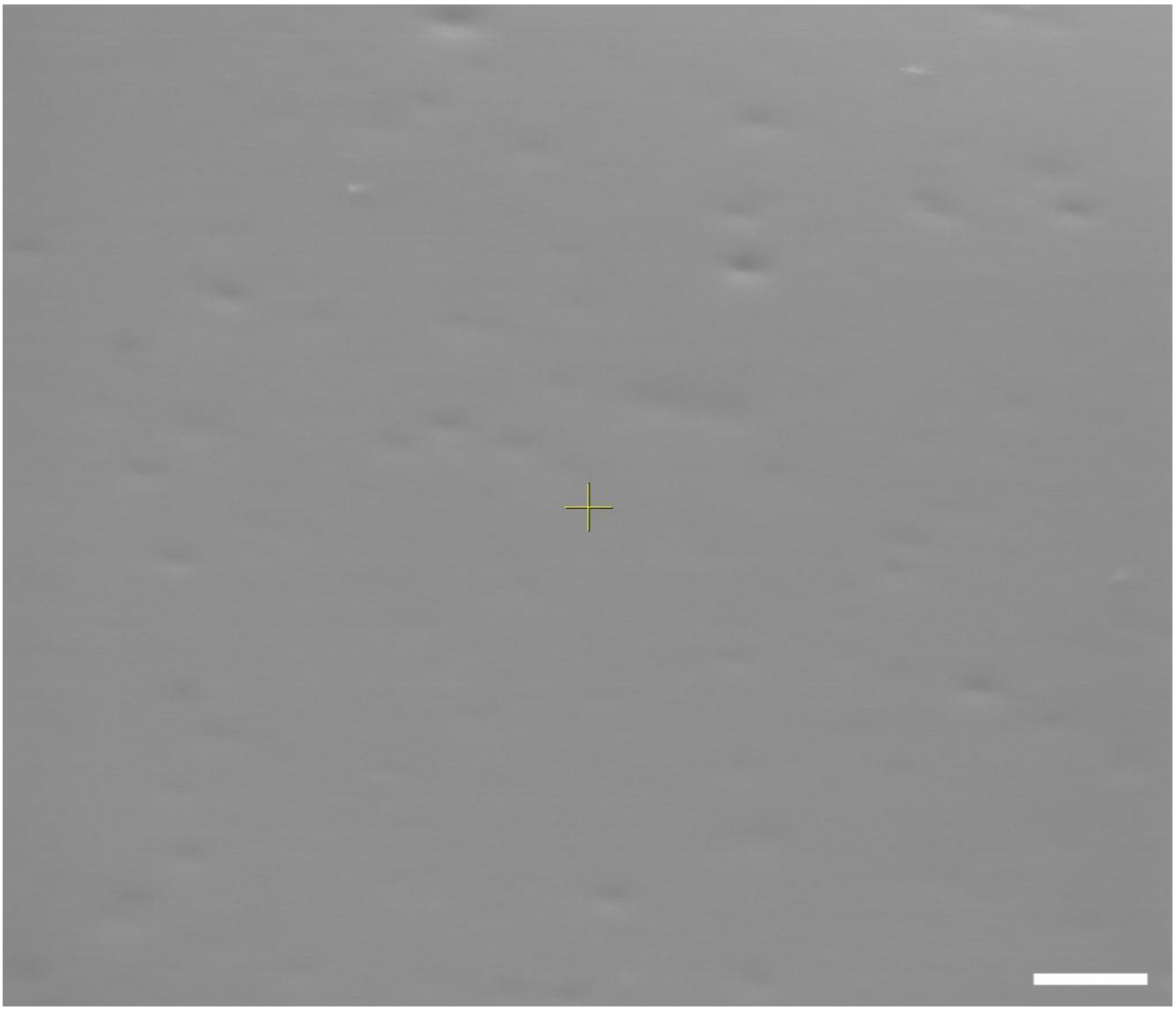

Fig. S1 SEM image of a 24 µm tall channel using unspun SU-8 at 8.16% transparent and 225s of UV exposure. Scale Bar: 20 µm